

Notice of References Cited

Application/Control No.

10/042,509

Applicant(s)/Patent Under
Reexamination
ELLIOTT ET AL.

Examiner

Sean P. Shechtman

Art Unit

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,590,051	12-1996	Yokozawa	364/496
	B	US-5,911,858	06-1999	Ruffner	204/192.27
	C	US-6,049,661	04-2000	Hayakawa	395/500.34
	D	US-5,246,529	09-1993	Fukasawa et al.	156/643
	E	US-6,156,654	12-2000	Ho et al.	438/683
	F	US-5,421,934	06-1995	Misaka et al.	216/59
	G	US-5,060,595	10-1991	Ziv et al.	118/772
	H	US-6,199,029	03-2001	Ohta	703/1
	I	US-5,523,543	06-1996	Hunter Jr. et al.	219/121.62
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Suzuki, "A Monte Carlo simulation of laser ablation during the laser pulse: Cl2(s) ablation dynamics for neutral beam etching" 6/3/1996 - 6/5/1996, Plasma Science, IEEE International Conference.
	V	Misaka, "Dry Etching Topography Simulator with a New Surface Reaction Model: MODERN" November 1995, IEEE Transactions On Electron Devices, Vol. 42, No. 11, pages 1903-1911.
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.